

INFORMATION DISCLOSURE STATEMENT

Applicant	:	Masuda et al.
App. No	:	10/564,510
Filed	:	January 12, 2006
For	:	POSITIVE PHOTORESIST COMPOSITION AND METHOD OF FORMING RESIST PATTERN
Examiner	:	John S. Y. Chu
Art Unit	:	1752

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

Enclosed for filing in the above-identified application is a PTO/SB/08 Equivalent listing 14 references to be considered by the Examiner. Also enclosed are 8 foreign patent references and/or non-patent literature as listed on the Information Disclosure Statement.

This Information Disclosure Statement is being filed before the mailing date of a final action and before the mailing date of a Notice of Allowance.

CERTIFICATION UNDER 37 C.F.R. § 1.97(e)(1)

I hereby certify that each item of information contained in this Statement was first cited in a communication from a foreign Patent Office in a counterpart foreign application not more than three months prior to the filing of this Information Disclosure Statement.

Thus, no fee is required as set forth in 37 C.F.R. § 1.97(c).

Respectfully submitted,

KNOBBE, MARTENS, OLSON & BEAR, LLP

Dated: December 14, 2006

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT <i>(Multiple sheets used when necessary)</i>	Application No.	10/564,510
	Filing Date	January 12, 2006
	First Named Inventor	Yasuo Masuda
	Art Unit	1752
SHEET 1 OF 1		Attorney Docket No. SHIGA7.036APC

U.S. PATENT DOCUMENTS					
Examiner Initials	Cite No.	Document Number Number - Kind Code (if known) Example: 1,234,567 B1	Publication Date MM-DD-YYYY	Name of Patentee or Applicant	Pages, Columns, Lines Where Relevant Passages or Relevant Figures Appear
	1	2002/0012865 A1	01-31-2002	Suzuki et al.	
	2	2002/0182531 A1	12-05-2002	Mizuta et al.	
	3	5,683,851	11-04-1997	Tan et al.	
	4	6,265,129 B1	07-24-2001	Takahashi et al.	
	5	6,274,287 B1	08-14-2001	Moriuma et al.	
	6	6,566,031 B1	05-20-2003	Suzuki et al.	

FOREIGN PATENT DOCUMENTS						
Examiner Initials	Cite No.	Foreign Patent Document Country Code-Number-Kind Code Example: JP 1234567 A1	Publication Date MM-DD-YYYY	Name of Patentee or Applicant	Pages, Columns, Lines Where Relevant Passages or Relevant Figures Appear	T ¹
	7	EP 0 598 320 A2	05-25-1994	Osaki et al.		
	8	JP 06-003815	01-14-1994	Fuji Photo Film Co. Ltd.		✓
	9	JP 07-159990	06-23-1995	Nippon Zeon Co. Ltd.		✓
	10	JP 10-069077	03-10-1998	Shin Etsu Chem. Co. Ltd.		✓
	11	JP 10-153857	06-09-1998	Nippon Zeon Co. Ltd.		✓
	12	JP 10-232492	09-02-1998	Sumitomo Chem. Co. Ltd.		✓

NON PATENT LITERATURE DOCUMENTS			
Examiner Initials	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ¹
	13	Office Action dated October 24, 2006 for counterpart Japanese Patent Application No. 2003-197873.	
	14	Office Action dated October 31, 2006 for counterpart Japanese Patent Application No. 2003-197874.	

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Examiner Signature	Date Considered
*Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	

T¹ - Place a check mark in this area when an English language Translation is attached.